LIFT – SYSTEM SETUP

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Laser Induced Forward Transfer (LIFT)

- Transfer slide with absorbance layer (Ti, Au etc.)
- Thin absorber layer (60 – 100 nm)
- Distance between transfer and receiver slide: 100 µm – 2 mm
- Arbitrary patterning possible

- Laser source: pulsed Laser (e.g. microchip Laser, 1064 nm or 355 nm, pulse width 1 ns)
LIFT concept
LIFT System (Size: 800 x 500 x 700 mm³)

View of Laser compartment and process chamber

Tool in housing
LIFT System (demonstrator) I
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